

Application No.: 10/758,966  
Office Action Mailed On: September 7, 2006  
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Attorney Docket No.: F125

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**Amendments to the Specification:**

Please amend the following paragraph as follows:

[1053] A door 60 is opened for inserting sample 22 on stage 24 which may be heated or cooled, ~~and also for servicing the reservoir 50.~~ The door is interlocked so that it cannot be opened if the system is under vacuum. The high voltage power supply provides an appropriate acceleration voltage to electrodes in ion beam column 16 for energizing and focusing ion beam 18. When it strikes the work piece, material is sputtered, that is physically ejected, from the sample. Dual beam systems are commercially available, for example, from FEI Company, Hillsboro, Oregon, the assignee of the present application. The invention can also be practiced on single or multiple beam systems. It is preferable to use charge neutralization when repairing a mask, because the insulating substrate tends to accumulate electrical charge which can displace the landing position of the beam on the surface, and consequently alter the location of the repair. For example, charge can be neutralized using an electron flood gun or an ion generator, as described in US Prov. Pat. App. No. 60/411,699.

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